

	L #	Hits	Search Text
1	L1	5	(exposure near2 (apparatus or system)) and lithograph\$3 and (maintenance same floor)
2	L2	21	(exposure near2 (apparatus or system)) and (maintenance same floor)
3	L3	16	2 not 1
4	L4	59	(exposure near2 (apparatus or system)) and (clearance near4 (area or space))
5	L5	58	4 not 2
6	L6	12	5 and lithograph\$3
7	L7	3790	(exposure near2 (apparatus or system)) and lithograph\$3
8	L8	101880	(mask or reticle) and (wafer or substrate)
9	L9	3051	7 and 8
10	L10	23317	(transport\$5 or transfer\$4 or moving or move or moved) same rail same (ceiling or above or high)
11	L11	6	10 and 9
12	L12	82830	(transport\$5 or transfer\$4 or moving or move or moved) same rail\$5

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	L #	Hits	Search Text
13	L13	51	9 and 12
14	L14	45	13 not 11
15	L15	135869 1	coat\$3 or develop\$4
16	L16	31	14 and 15